

EXPLORING NEW WAYS OF CHEMICAL VAPOR DEPOSITION TECHNOLOGY TO PRODUCE GRAPHENE

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Abstract

Chemical vapor deposition (CVD) is a very popular technology to produce monolayer graphene. However, this technology is associated with relatively high temperatures and supersaturation carbon precursor conditions to produce a graphene monolayer. The goal of this work is to explore different ways of growing graphene on copper over silicon by means of thermally activated chemical vapor deposition using a low precursor pressure. Growing processes were performed in a reactor with a quartz tube oven at high vacuum conditions. The activated copper substrate was exposed to methane gas at a low pressure and annealed below 1000 °C. Results indicate a possible solution of Cu on a Ni barrier (grown in order to avoid diffusion of Cu into c-Si) forming a polycrystalline surface Cu/Ni thin layer, which favors the nucleation of graphene. During the annealing Ni/Cu drops are formed clearing large areas of silicon substrate ($10^4 \mu\text{m}^2$, Fig. 1). The characterization by Raman spectroscopy, X-Ray spectroscopy (EDS) and scanning electron microscopy (SEM) evidenced that large-areas of crystalline silicon appeared 99% copper free and coated by graphene. The Raman analysis of these areas assessed the only presence of graphene of one-two layers by showing the characteristic 2D band and the ratio $2\text{D}/\text{G} \geq 1$ (Fig. 2). The direct growth of graphene on silicon wafers without transferring facilitates the application of lithographic processes and the possibility to produce graphene-based electronic devices.

References

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Figures

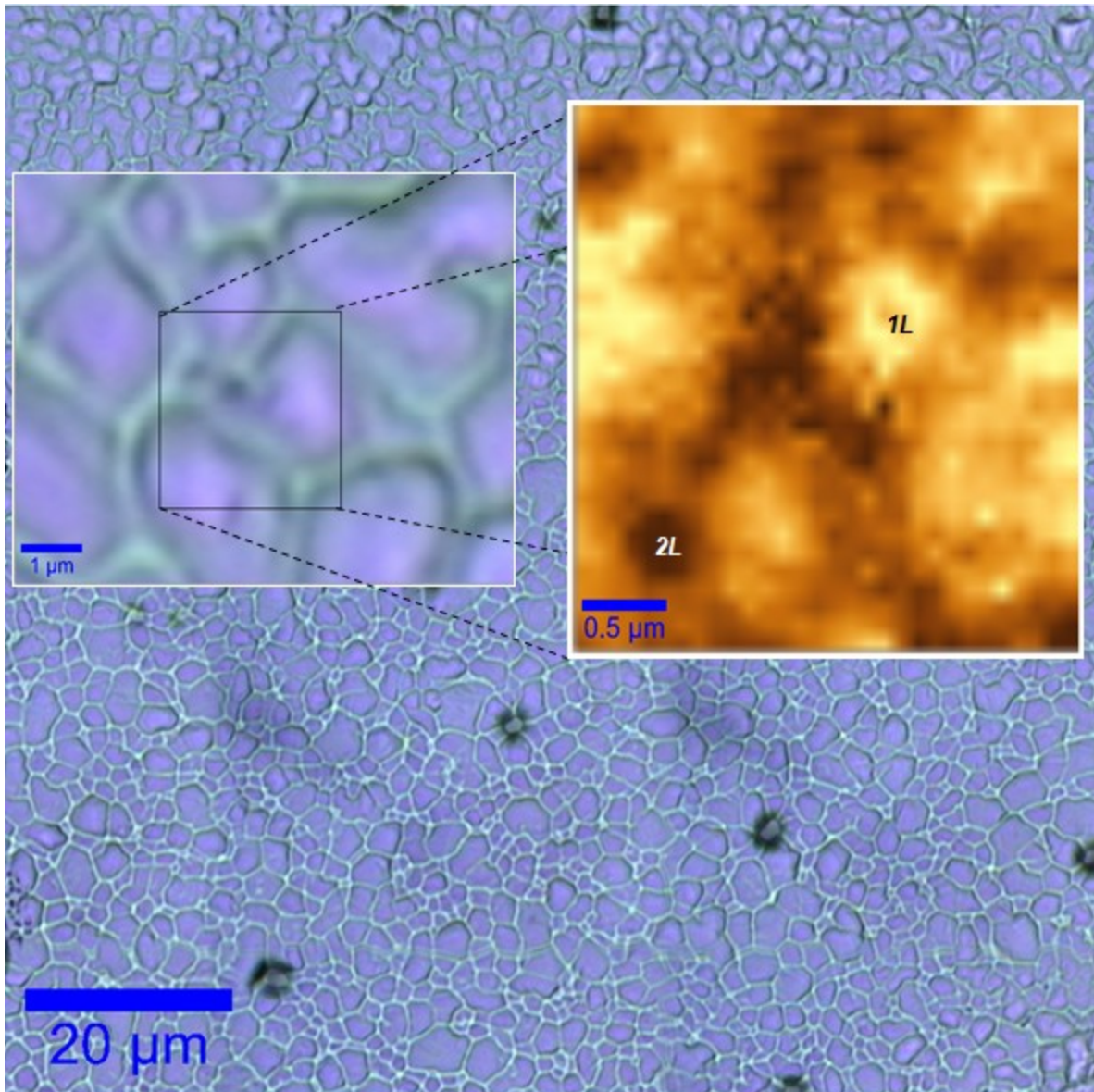


Fig. 1. Raman mapping of areas about $10^4 \mu\text{m}^2$. The surface is covered with 80% monolayer graphene and 20% of bilayer graphene.

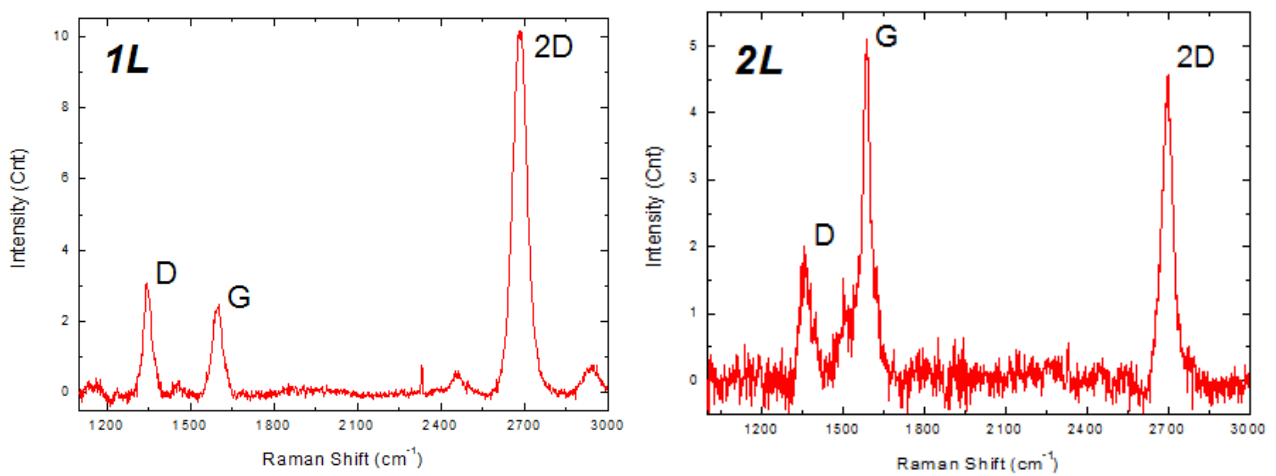


Fig. 2. Raman spectra of monolayer and bilayer graphene. Ratio between 2D/G peaks are much bigger than 1 in most of monolayers.